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				Application Number	10/596,626-Conf. #8534
				Filing Date	June 19, 2006
				First Named Inventor	Karl-Heinz Schuster
				Art Unit	N/A
				Examiner Name	Not Yet Assigned
Sheet	1	of	1	Attorney Docket Number	01641/0204258-US0

U.S. PATENT DOCUMENTS					
Examiner Initials*	Cite No. <sup>1</sup>	Document Number	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Number-Kind Code <sup>2</sup> (#known)			
AA*	US-6,717,722		04-06-2004	Shafer et al.	
AB*	US-2005/0190455-A1		09-01-2005	Rostalski et al.	
AC*	US-2005/0225737-A1		10-13-2005	Weissenrieder et al.	
AD*	US-2006/0012885-A1		01-19-2006	Beder et al.	
AE*	US-6,995,930		02-07-2006	Shafer et al.	
AF*	US-2006/0221456-A1		10-05-2006	Shafer et al.	
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AH*	US-2002/0102497-A1		10-07-2003	Sparrow	
AI*	US-4,861,148		08-29-1989	Sato et al.	
AJ*	US-6,025,115		02-15-2000	Komatsu et al.	

FOREIGN PATENT DOCUMENTS					
Examiner Initials*	Cite No. <sup>1</sup>	Foreign Patent Document	Publication Date MM-DD-YYYY	Name of Patentee or Applicant of Cited Document	Pages, Columns, Lines, Where Relevant Passages or Relevant Figures Appear
		Country Code <sup>3</sup> -Number <sup>4</sup> -Kind Code <sup>5</sup> (#known)			
BA	WO-2004/019128		03-04-2004	Nikon Corporation	✓
BB	WO-2005/081067		09-01-2005	CARL ZEISS SMT AG	✓
BC	WO-2005/106589		11-10-2005	CARL ZEISS SMT AG	✓
BD	EP-0 475 020-A		03-18-1992	International Business Machines Corporation	✓
BE	WO-2005/059654		06-30-2005	Carl Zeiss SMT AG	✓

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NON PATENT LITERATURE DOCUMENTS					
Examiner Initials	Cite No. <sup>1</sup>	Include name of the author (in CAPITAL LETTERS), title of the article (when appropriate), title of the item (book, magazine, journal, serial, symposium, catalog, etc.), date, page(s), volume-issue number(s), publisher, city and/or country where published.			T <sup>6</sup>
CA	Smith, B. W. et al., "Water Immersion Optical Lithography for the 45nm Node", <i>Optical Microlithography XVI, Proceedings of SPIE</i> (2003) Vol. 5040, 679-689				
CB	Smith, B.W. et al., "Approaching the numerical aperture of water-Immersion lithography at 193nm", <i>Optical Microlithography XVII, Proceedings of SPIE</i> , Vol. 5377, 273-284				
CC	Burnett, J.H. et al., " High Index Materials for 193 nm and 157 nm Immersion Lithography", <i>International Symposium on Immersion &amp; 157 nm Lithography</i> , Vancouver, 8/2/2004				

\*EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP 609. Draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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